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Attorney Docket No. 042390.P4514D

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re the Patent Application of:

Brian S. Doyle

Serial No. 09/416,501

Filed: October 8, 1999

Examiner: Ortiz, Edgardo

Art/Unit: 2815

For: **METHOD FOR DELAMINATING A
THIN FILM USING NON-THERMAL
TECHNIQUES**

PRELIMINARY AMENDMENT

Box CPA
Commissioner for Patents
Washington, D.C. 20231-9998

Dear Sir:

In connection with the continuation application filed herewith regarding the above-referenced Application, the Applicant respectfully requests consideration of the following amendments and remarks.

IN THE CLAIMS

Please amend the claims as follows:

28. (Amended Twice) An apparatus comprising:
a first substrate portion having a dielectric layer on a surface, the first substrate portion formed as a film of less than an entire portion of a starting material by demarcating a film thickness through an ion implantation into the starting material and separating the first substrate portion from the starting material; and

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